

## Electronic Supplementary Information

### Permeation properties and hydrothermal stability of Allylhydridopolycarbosilane (AHPCS)-derived Silicon Carbide (SiC) membranes

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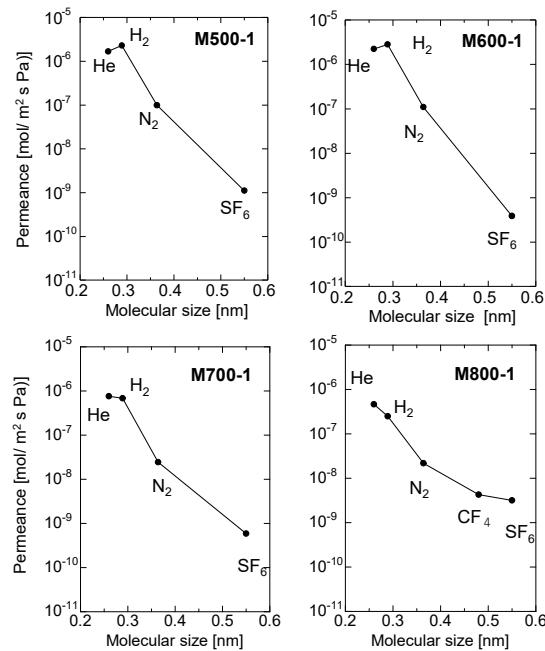
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**AHPCS membrane performance at 200 °C before hydrothermal treatment (HT) at different firing temperatures.**

The permeance of single gas through an AHPCS-derived membrane was measured at a temperature of 200 °C. Single gas permeance is useful for evaluating the pore size distribution of membranes and is the simplest method for determining membrane quality. Generally, all membranes showed decreased permeance for large-sized gases, indicating typical molecular sieving properties. The H<sub>2</sub>/N<sub>2</sub> selectivity ranged from 10–20 with excellent H<sub>2</sub> permeance higher than 10<sup>-6</sup> mol/(m<sup>2</sup> s Pa).



**Fig. S1** Single gas permeance at 200 °C as a function of molecular size through AHPCS membranes formed at different firing temperatures.

**Table S1.** AHPCS membrane performance at 200 °C before hydrothermal treatment (HT) at different firing temperatures.

Membranes	Permeance (10 <sup>-8</sup> [mol / (m <sup>2</sup> s Pa)])			
	He	H <sub>2</sub>	N <sub>2</sub>	SF <sub>6</sub>
M500-1	168	230	10	0.11
M600-1	223	282	11	0.04
M700-1	76	68.3	2.44	0.06
M800-1	46	24.9	2.18	0.32

Membranes	Seletivity [-]		
	He/H <sub>2</sub>	H <sub>2</sub> /N <sub>2</sub>	H <sub>2</sub> /SF <sub>6</sub>
M500-1	0.73	23.23	2090.91
M600-1	0.79	25.66	7287.62
M700-1	1.11	27.98	1159.93
M800-1	1.86	11.43	78.61

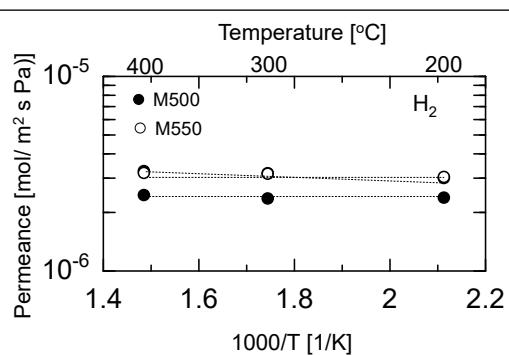
### Activation energy of H<sub>2</sub> for each membrane.

The temperature dependency (200–400 °C) of H<sub>2</sub> permeance was also evaluated on the AHPCS-derived membrane and used to obtain the activation energy of H<sub>2</sub>. Notably, the activation energy was obtained by regressing the temperature dependence of the H<sub>2</sub> permeance for temperatures ranging from 200 to 400 °C using the translation model.<sup>1</sup>

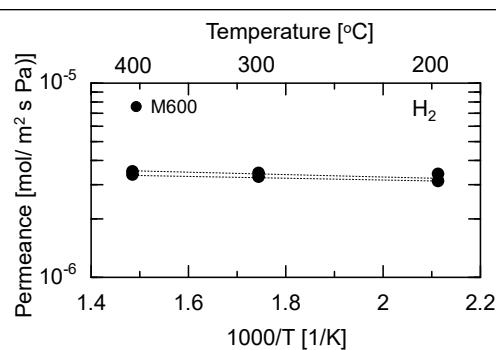
$$P_i = \frac{k_{0,i}}{\sqrt{M_i RT}} \exp\left(-\frac{E_{p,i}}{RT}\right),$$

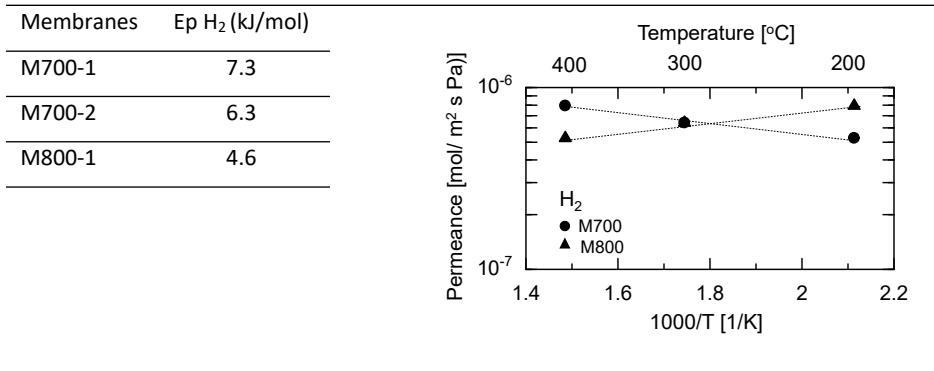
where  $k_{0,i}$  is the pre-exponential factor;  $E_{p,i}$  is the permeation activation energy;  $M_i$  is the molecular weight of the  $i$ th component;  $R$  is the gas constant; and  $T$  is the absolute temperature.<sup>2</sup>

Membranes	Ep H <sub>2</sub> (kJ/mol)
M500-1	2.6
M500-2	3.6
M550-1	2.8
M550-2	2.1



Membranes	Ep H <sub>2</sub> (kJ/mol)
M600-1	2.4
M600-2	3.6
M600-3	3.4

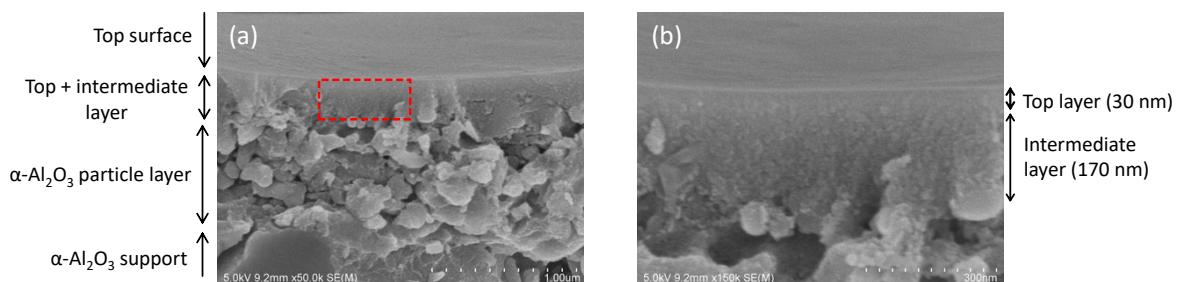




**Fig. S2.** Activation energy of H<sub>2</sub> for each membrane

**FESEM image of cross section of low magnification (x50,000) (a), and of high magnification (x150,000) (b)**

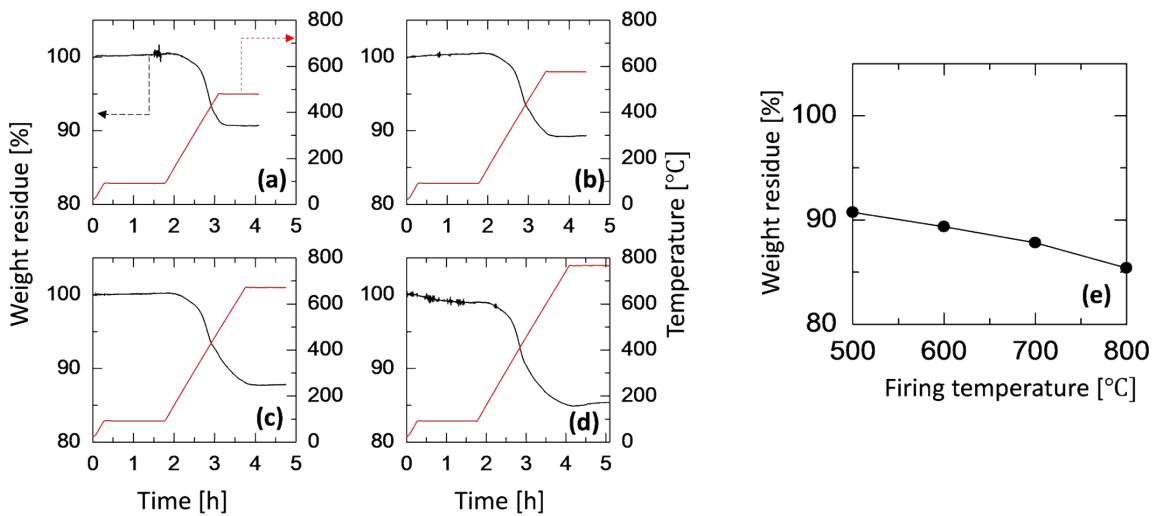
FESEM images illustrating the cross section of low and high magnification of the M700 membrane are presented in Figs. S3 (a) and (b), respectively. The estimated thickness of the top layer, including the intermediate layer, is approximately 200 nm (Fig. S3 (a)). Fig. S3(b) shows the SEM image of high magnification of the area surrounded by the dotted lines in Fig. S3(a), indicating top layer thickness is around 30 nm. This thin top layer has the potential to impart the resulting membrane with high gas permeability and molecular sieving properties.



**Fig. S3** FESEM image of cross section of low magnification (x50,000) (a), and of high magnification (x150,000) (b)

**DTG curves of weight residue of AHPSCS at different temperatures.**

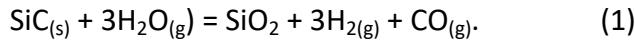
The process of turning AHPSCS precursors into ceramics involves three main stages. First, polymer phase ( $T \leq 400^\circ\text{C}$ ) consists mainly of connected polymer chains. Second, transition phase ( $400^\circ\text{C} < T < 700^\circ\text{C}$ ) involves the decomposition of the organic groups. This phase is a transition for getting the materials ready for ceramic conversion. Third, in ceramic phase ( $T \geq 700^\circ\text{C}$ ), the material enters the ceramic phase. We performed TGA (Thermogravimetric Analysis) measurements to assess thermal stability. The steps for TG measurements mirrored those of membrane fabrication. Initially, the sample underwent heating at  $100^\circ\text{C}$  for 1.5 hours to eliminate any water content present on the powder. Subsequently, the temperature was raised to various levels ( $500\text{--}800^\circ\text{C}$ ) at a rate of  $5^\circ\text{C}$  per minute and held at each temperature for 1 hour under  $\text{N}_2$ . As shown in the time course (Figs. S4 (a), (b), (c), (d)), the weight residue remained constant after reaching each temperature, confirming the thermal stability. Fig S4 (e) shows the summary of weight residue after holding 1 h at different temperatures. The material undergoes a gradual reduction in weight as the temperature increases, signifying a process of thermal decomposition and/or transformation from polymer ceramic phase, which induces the formation of a denser network within the material.



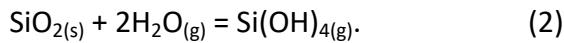
**Fig. S4** Time course of thermal treatment (a)  $500^\circ\text{C}$ , (b)  $600^\circ\text{C}$ , (c)  $700^\circ\text{C}$ , (d)  $800^\circ\text{C}$ , and (e) weight residue of AHPSCS at different temperature. ( $\text{N}_2$  flow rate 50 ml/min, heating rate of  $5^\circ\text{C}/\text{min}$ ).

**Schematic illustration of surface structure changed after hydrothermal treatment.**

The steam oxidation of SiC at high temperatures (1400–1800 °C) can be categorized into two different processes, known as SiO<sub>2</sub> formation and its volatilization.<sup>3</sup> The formation of both a condensed SiO<sub>2</sub> oxide and volatile phases, such as Si(OH)<sub>4</sub>, is induced at the same time. SiC reacts with water vapor to form SiO<sub>2</sub> on the SiC surface via the following reaction:



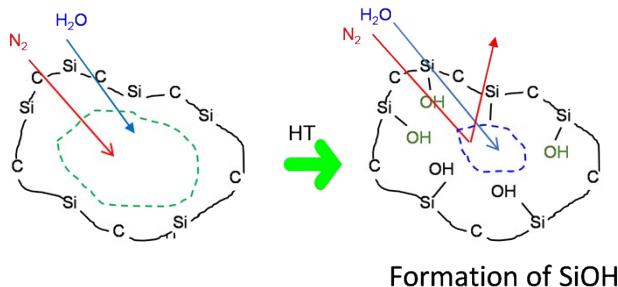
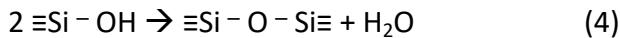
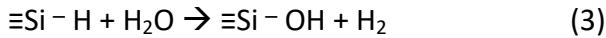
On the surface, the oxide scale reacts with water vapor at high temperatures and undergoes volatilization via, the following reaction:



In the meantime, at the interface, SiC reacts to form SiO<sub>2</sub>, with H<sub>2</sub>O or oxidizing OH• or H• radicals.<sup>4</sup> This reaction (Eq. 1) also reportedly occurred at 600 °C although conversion to silica was low around 1%,<sup>5</sup> and it may have occurred at 400 °C.

SiC-based membranes are expected to be more hydrothermally stable than SiO<sub>2</sub> and organosilica membranes due to the incorporation of carbon elements in the silica structure. The decrease in N<sub>2</sub> permeance can be attributed to the formation of -OH (Si-OH) groups on the surface of the membrane pores. The pore size of the membrane decreases after HT due to water vapor oxidation. This reduction in pore size results in decreased permeation of larger gas molecules, such as N<sub>2</sub>. Specifically, the molecular sizes follow the order N<sub>2</sub> > H<sub>2</sub>O > He, with sizes of (kinetic diameter: 0.364<sup>6</sup> nm, 0.265<sup>7</sup> nm, 0.26<sup>8</sup> nm), respectively. The obtained results align with findings from experiments conducted using carbonized-template molecular sieve silica membranes under hydrothermal conditions (400°C, steam: 34 kPa).<sup>9,10</sup>

Upon exposure to high temperatures of steam, the AHPSCS membrane undergoes a reaction with water vapor, forming Si-OH groups. Si-H groups oxidize (Eq. 3) to form Si-OH groups, which further undergo condensation to create Si-O-Si linkers (Eq. 4), resulting in a denser network structure. This densification leads to a reduction in pore size, limiting the movement of gas molecules through the membrane and subsequently lowering the gas permeation rate (Fig. S3). The observed changes are consistent with the triethoxysilane (TRIES) silica membrane network structure, where a decrease in Si-H groups correlates with a denser network under hydrothermal conditions.<sup>11</sup>



**Fig. S5.** Schematic illustration of surface structure changed after hydrothermal treatment.

**Permeance and selectivity at 200 °C before and after hydrothermal treatment (HT) of membrane firing from 500–800 °C.**

The gas permeance ratio determines the selectivity and is commonly employed as an index for evaluating membrane quality. The selectivity before feeding water vapor, indicated as “0HT,” is a crucial parameter. Similarly, the selectivity after the 1st, 2nd and 3rd HT is denoted as “1HT,” “2HT” and “3HT.” After subjecting the membranes to HT, the selectivity of He/H<sub>2</sub> increased for M500 to M700, but decreased for M800. This was attributed to the denser membrane pores in M800, making it easier for He to permeate than H<sub>2</sub>. In contrast, the H<sub>2</sub>/N<sub>2</sub> selectivity reached its peak at M600 after HT, showing an almost four-fold increase compared with that before HT. However, the selectivity of H<sub>2</sub>/SF<sub>6</sub> decreased for all membranes after HT, as pinholes were formed during the treatment, leading to reduced selectivity.

The permeance values of He, N<sub>2</sub>, and SF<sub>6</sub>, were measured before and after 3HT. After subjecting the membranes to three HT cycles, the permeance of all gases decreased, except for that of SF<sub>6</sub>. The reduction in permeance can be attributed to the shrinkage of the membrane pores, whereas the increase in SF<sub>6</sub> permeance was attributed to the presence of pinholes.

**Table S2.** Comparison permeance and selectivity at 200 °C before and after hydrothermal treatment (HT) of membrane firing from 500–800 °C.

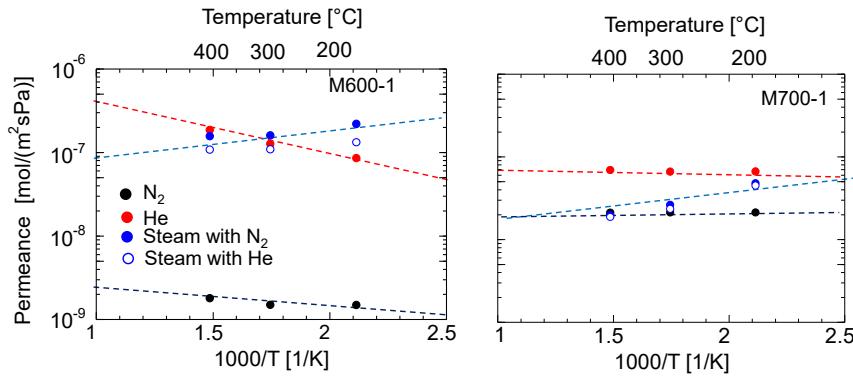
Membranes	Permeance ( $10^{-8}$ [mol /( $\text{m}^2 \text{s Pa}$ )])															
	He				H <sub>2</sub>				N <sub>2</sub>				SF <sub>6</sub>			
	0 HT	1 HT	2 HT	3 HT	0 HT	1 HT	2 HT	3 HT	0 HT	1 HT	2 HT	3 HT	0 HT	1 HT	2 HT	3 HT
M500-1	168	54	46.8	44	230	60	52.7	46	10	2.1	2.04	2	0.11	0.2	0.3	0.3
M600-1	223	75	52	40.5	282	51.2	30.1	20.9	11	0.6	0.4	0.28	0.04	0.03	0.03	0.1
M700-1	76	46.8	19.3	14.1	68.3	52.7	9.27	3.3	2.44	2.04	0.45	0.33	0.06	0.2	0.1	0.1
M800-1	46	28.9	22.2	16.2	24.9	11.7	9.74	9.43	2.18	0.64	0.74	0.71	0.32	0.33	0.34	0.3

Membranes	Selectivity [-]											
	He/H <sub>2</sub>				H <sub>2</sub> /N <sub>2</sub>				H <sub>2</sub> /SF <sub>6</sub>			
	0 HT	1 HT	2 HT	3 HT	0 HT	1 HT	2 HT	3 HT	0 HT	1 HT	2 HT	3 HT
M500-1	0.73	0.90	0.89	0.97	23.23	27.85	25.80	23.72	2090.91	294.18	192.26	176.54
M600-1	0.79	1.46	1.73	1.94	25.66	<b>85.51</b>	85.17	74.28	7287.62	1779.83	947.78	170.20
M700-1	1.11	0.89	2.09	4.24	27.98	25.83	20.60	9.94	1159.93	192.34	86.16	32.87
M800-1	1.86	2.45	2.28	1.72	11.43	18.52	13.23	13.20	78.61	35.87	28.70	28.89

### **Temperature dependence of gas permeance through microporous APCS membranes.**

In this study, the temperature dependence of He, N<sub>2</sub>, and H<sub>2</sub>O permeance was examined for APCS membranes fired at 550, 600, and 700 °C. As shown in Fig. S6 similar to M550 in Fig. 11, M600 and M700 also showed a linear relationship between the He permeance and reciprocal temperature, suggesting an activated diffusion mechanism.<sup>12</sup> Significantly, H<sub>2</sub>O showed decreased permeance with increasing temperature, which again confirmed the surface diffusion properties of H<sub>2</sub>O.



**Fig. S6.** Temperature dependence at various firing temperatures membranes for M600-1 (left) and M700-1 (right).

**Comparison of H<sub>2</sub>O/N<sub>2</sub>, H<sub>2</sub>O/H<sub>2</sub>, and H<sub>2</sub>O/He of AHPCS-SiC derived membranes with other membranes.**

**Table S3.** Comparison of H<sub>2</sub>O/N<sub>2</sub>, H<sub>2</sub>O/H<sub>2</sub>, H<sub>2</sub>O/He of AHPCS-SiC derived membranes with other membranes.

System	Material	Tempera ture [°C]	$p_{\text{water}}$ [kPa]	Water permeance [10 <sup>-8</sup> mol/(m <sup>2</sup> Pa s)]	Permeance ratio	Reference
H <sub>2</sub> O/N <sub>2</sub>	PCS	50			107	13
H <sub>2</sub> O/N <sub>2</sub>	TFN_SU (0.2)	30	98	67	564	14
H <sub>2</sub> O/N <sub>2</sub>	TFN CU (0.2)	30	98	72	639	14
H <sub>2</sub> O/N <sub>2</sub>	TFN_U (0.2)	30	98	58	485	14
H <sub>2</sub> O/H <sub>2</sub>	Zeolite A	200			270	15
H <sub>2</sub> O/H <sub>2</sub>	modernit	200			0.7	15
H <sub>2</sub> O/H <sub>2</sub>	zeolite T				~10	15
H <sub>2</sub> O/N <sub>2</sub>	Nafion-IL-SiO <sub>2</sub>	250	100	71	130	16
H <sub>2</sub> O/H <sub>2</sub>	Zeolite A	180	10		200	17
H <sub>2</sub> O/H <sub>2</sub>	Zeolite A	>240	10		<20	17
H <sub>2</sub> O/N <sub>2</sub>	BTESE	150	130-140	1100	320	18
H <sub>2</sub> O/N <sub>2</sub>	BTESE	100	130-140		1200	18
H <sub>2</sub> O/H <sub>2</sub>	BTESE	200	11	428	4.5	12
H <sub>2</sub> O/H <sub>2</sub>	BTESE	80			170	12
H <sub>2</sub> O/H <sub>2</sub>	BTESE	200	11	470	4.0	12

H <sub>2</sub> O/H <sub>2</sub>	BTESE	200	11	370	3.7	12
H <sub>2</sub> O/H <sub>2</sub>	BTESE	200	57	287	16.4	12
H <sub>2</sub> O/H <sub>2</sub>	BTESE	150	10	514	13	12
H <sub>2</sub> O/H <sub>2</sub>	BTESE	150	10	277	82	12
H <sub>2</sub> O/H <sub>2</sub>	BTESE	150	11	388	23	12
H <sub>2</sub> O/H <sub>2</sub>	BTESE	150	11	546	6.8	12
H <sub>2</sub> O/H <sub>2</sub>	BTESE	150	11	439	7.1	12
H <sub>2</sub> O/H <sub>2</sub>	BTESE	150	56	525	32	12
H <sub>2</sub> O/H <sub>2</sub>	BTESE	150	56	399	59	12
H <sub>2</sub> O/H <sub>2</sub>	BTESE	150	56	307	178	12
H <sub>2</sub> O/H <sub>2</sub>	BTESE	150	104	545	84	12
H <sub>2</sub> O/H <sub>2</sub>	Al-BTESE	80			76	19
H <sub>2</sub> O/N <sub>2</sub>	Al-BTESE	150	200-360		59	19
H <sub>2</sub> O/N <sub>2</sub>	i-BTESE	200	200	500	350	20
H <sub>2</sub> O/H <sub>2</sub>	silica	300	25	1.3	0.17	21
H <sub>2</sub> O/H <sub>2</sub>	NaA zeolite	240	46	30	0.18	22
H <sub>2</sub> O/H <sub>2</sub>	LTA	200	2	9.1	268	23
H <sub>2</sub> O/N <sub>2</sub>	BTESE	200	14	347	164	12
H <sub>2</sub> O/N <sub>2</sub>	BTESE	200	14	386	72	12
H <sub>2</sub> O/N <sub>2</sub>	BTESE	200	14	311	34	12
H <sub>2</sub> O/N <sub>2</sub>	BTESE	200	65	276	545	12
H <sub>2</sub> O/N <sub>2</sub>	BTESE	150	13	244	1697	12
H <sub>2</sub> O/N <sub>2</sub>	BTESE	150	14	426	502	12
H <sub>2</sub> O/N <sub>2</sub>	BTESE	150	14	331	1203	12
H <sub>2</sub> O/N <sub>2</sub>	BTESE	150	14	455	112	12
H <sub>2</sub> O/N <sub>2</sub>	BTESE	150	14	367	56	12
H <sub>2</sub> O/N <sub>2</sub>	BTESE	150	64	464	1161	12
H <sub>2</sub> O/N <sub>2</sub>	BTESE	150	64	305	1491	12
H <sub>2</sub> O/N <sub>2</sub>	BTESE	150	65	390	1445	12
H <sub>2</sub> O/N <sub>2</sub>	BTESE	150	107	546	>6700	12
H <sub>2</sub> O/N <sub>2</sub>	BTESE	80			3300	12

H <sub>2</sub> O/N <sub>2</sub>	Al-BTESE	80		1100	19
H <sub>2</sub> O/N <sub>2</sub>	Al-BTESE	150	200-360	740	19
H <sub>2</sub> O/N <sub>2</sub>	silica	300	30	1.4	15
H <sub>2</sub> O/N <sub>2</sub>	FAU zeolite	200	550	3190	8.0
H <sub>2</sub> O/N <sub>2</sub>	FAU zeolite	200	550	3990	7.0
H <sub>2</sub> O/He	TEFS-SiO <sub>2</sub>	500	90	0.27	25
H <sub>2</sub> O/N <sub>2</sub>	LTA	200	2	8.9	59
H <sub>2</sub> O/N <sub>2</sub>	Nafion 115	150	96	6	1190
H <sub>2</sub> O/N <sub>2</sub>	Nafion 115	150	180	10	1765
H <sub>2</sub> O/N <sub>2</sub>	Nafion 115	150	304	15	1515
H <sub>2</sub> O/N <sub>2</sub>	Nafion 115	150	377	29	1580
H <sub>2</sub> O/N <sub>2</sub>	AHPCS	400	125	130	27
H <sub>2</sub> O/N <sub>2</sub>	AHPCS	400	125	10	0.26
H <sub>2</sub> O/N <sub>2</sub>	AHPCS	500	125	13	25
H <sub>2</sub> O/N <sub>2</sub>	AHPCS	500	125	10	0.18
H <sub>2</sub> O/N <sub>2</sub>	AHPCS	300	125	34	118
H <sub>2</sub> O/N <sub>2</sub>	AHPCS	300	125	34	0.74
H <sub>2</sub> O/N <sub>2</sub>	AHPCS	400	125	11	25.8
H <sub>2</sub> O/He	AHPCS	400	125	10	0.26
H <sub>2</sub> O/N <sub>2</sub>	AHPCS	400	125	99	35.68
H <sub>2</sub> O/He	AHPCS	400	125	99	1.4
H <sub>2</sub> O/N <sub>2</sub>	AHPCS	400	125		12.44
H <sub>2</sub> O/He	AHPCS	400	125	4	0.07
H <sub>2</sub> O/N <sub>2</sub>	AHPCS	400	125	94	43.6
H <sub>2</sub> O/He	AHPCS	400	125	87	1.57
H <sub>2</sub> O/N <sub>2</sub>	AHPCS	400	125	10	16.7
H <sub>2</sub> O/He	AHPCS	400	125	6	0.135
H <sub>2</sub> O/N <sub>2</sub>	AHPCS	400	125	6	11
H <sub>2</sub> O/He	AHPCS	400	125	4	0.086
H <sub>2</sub> O/N <sub>2</sub>	AHPCS	400	125	53	102.45
H <sub>2</sub> O/He	AHPCS	400	125	26	0.433

H <sub>2</sub> O/N <sub>2</sub>	AHPCS	400	125	167	26	This work
H <sub>2</sub> O/He	AHPCS	400	125	131	0.7	This work
H <sub>2</sub> O/N <sub>2</sub>	AHPCS	400	125	22	48.1	This work
H <sub>2</sub> O/He	AHPCS	400	125	12	0.26	This work

## References

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